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# Thermal noise in 3<sup>rd</sup> generation gravitational wave detectors

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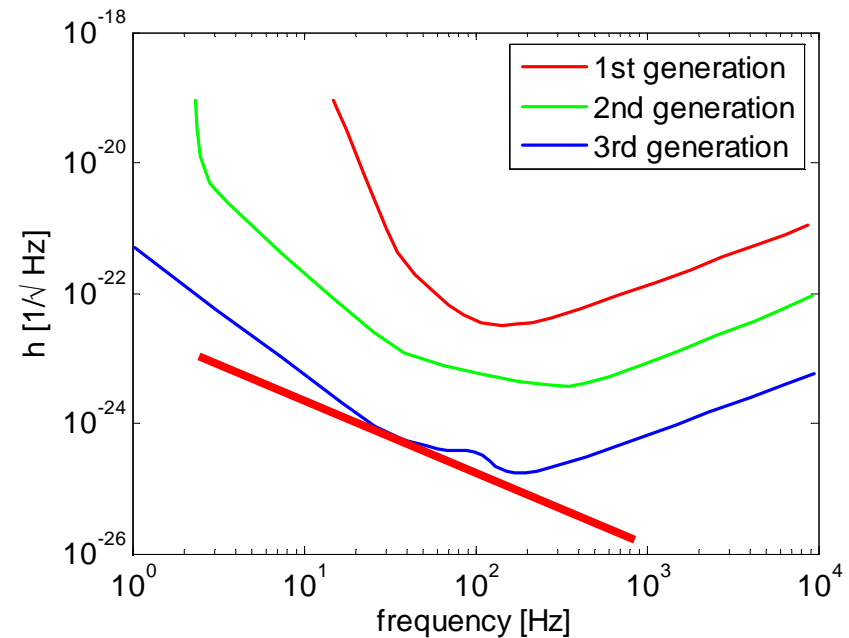
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# Introduction

- currently design study in Europe concerning a 3<sup>rd</sup> generation detector (Einstein Telescope - ET)
- improvement of roughly a factor of 10 between different generations of GWD
- 3<sup>rd</sup> generation gravitational wave detectors will be limited by several kinds of noise
- critical limitation:
  - seismic noise (gravity gradient)
  - thermal noise



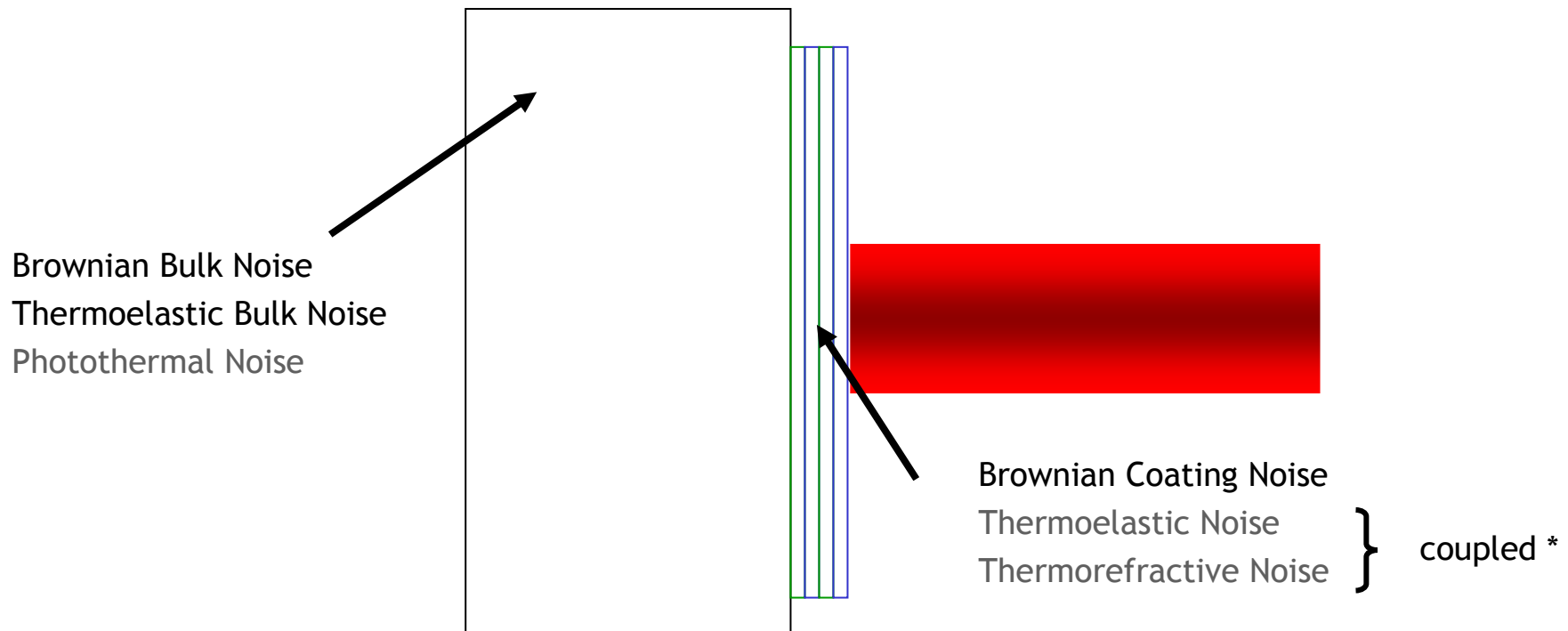
# Thermal Noise

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- thermal noise is dependent on
  - temperature  $\leftrightarrow$  thermal energy
  - mechanical loss  $\leftrightarrow$  spectral distribution
  - spatial distribution  $\leftrightarrow$  inhomogeneous losses
- minimum noise will be achieved for low mechanical loss at lowest possible temperatures
- lossy parts need to be far away from the interaction laser-surface

# Thermal Noise

- main contribution arises from:



\* [Evans et al. 2008]

# Bulk Thermal Noise

- Brownian thermal noise

$$S_X(f, T) = \frac{2k_B T}{\pi^{3/2} f} \times \frac{1 - \sigma^2}{w Y} \times \phi_{\text{substrate}}(f, T)$$

[Liu, Thorne 2000]

- thermoelastic noise

$$S_{TE}(f, T) = \frac{8}{\sqrt{2\pi}} \alpha^2 (1 + \sigma)^2 \frac{k_B T^2 r_0}{\kappa} \times J(\Omega)$$

[Rowan et al. 2000, Aspen Meeting]

[Cerdonio et al. 2001]

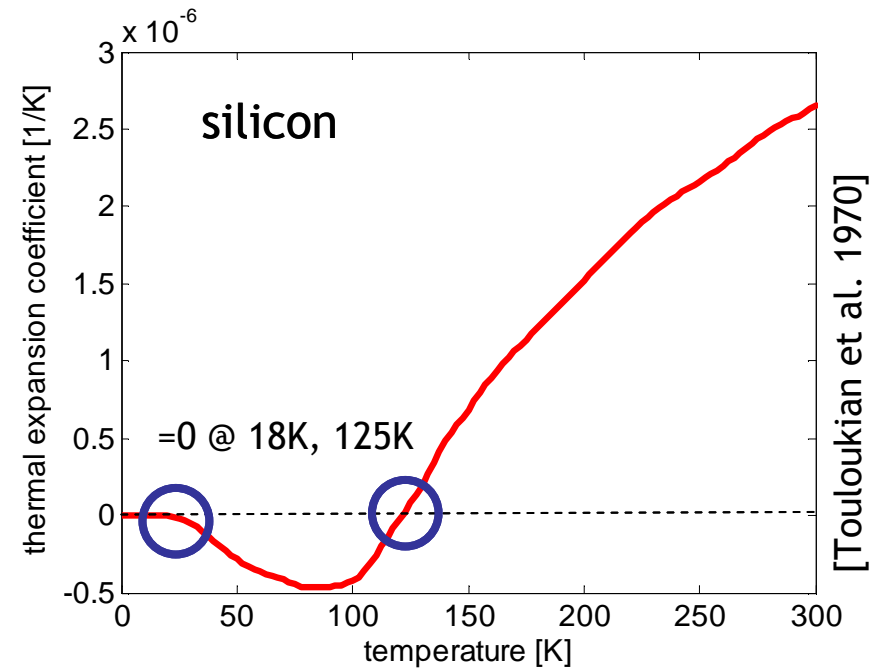
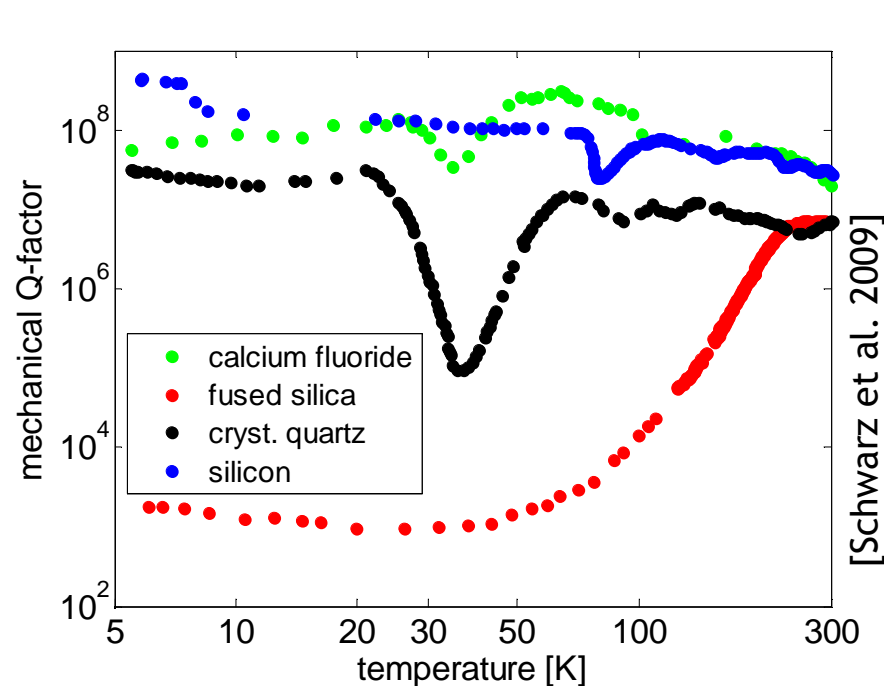
$$J(\Omega) = \sqrt{\frac{2}{\pi^3}} \int_0^{\infty} du \int_{-\infty}^{+\infty} dv \frac{u^3 e^{-u^2/2}}{(u^2 + v^2)[(u^2 + v^2)^2 + \Omega^2]}$$

correction term  
for non-adiabatic  
case

$$\Omega = \frac{\omega}{\omega_c} \quad \omega_c = \frac{\kappa}{\rho C r_0^2}$$

# Bulk Thermal Noise

- material selection is driven by thermal and mechanical properties

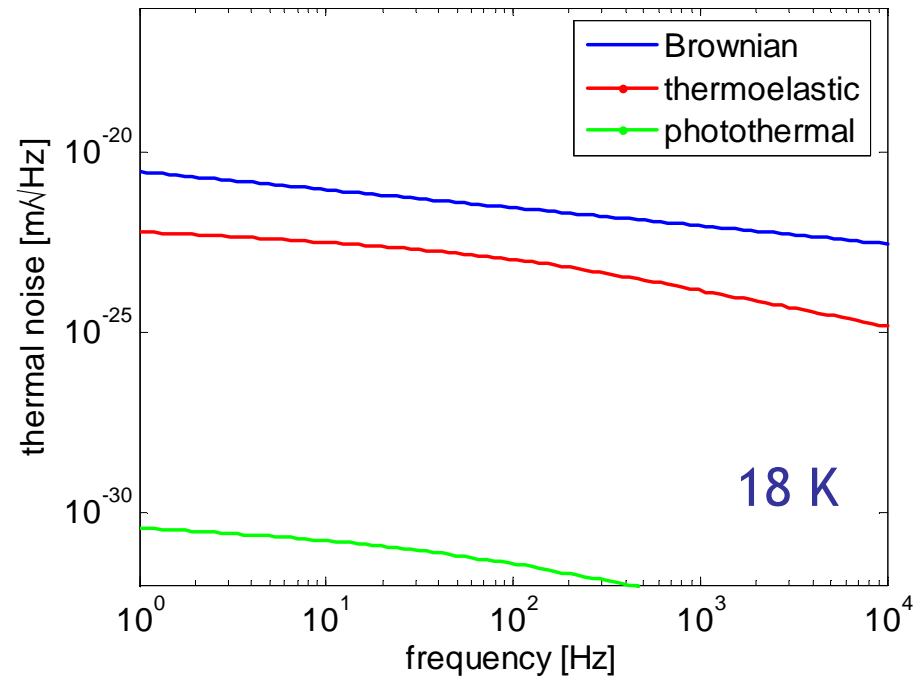
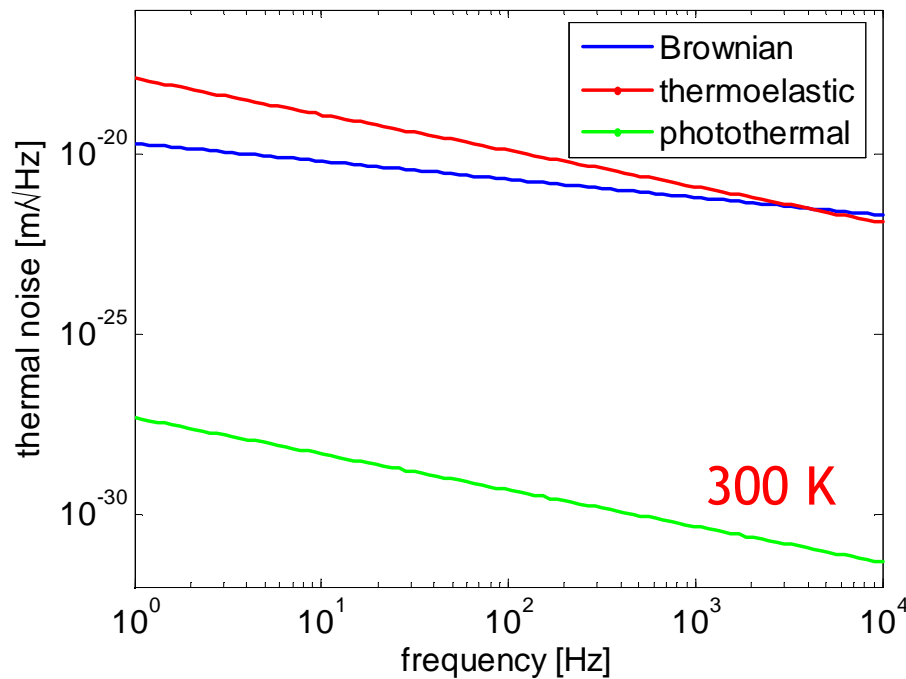


- silicon has excellent properties for low noise optics

[Winkler et al., Phys. Rev. A 44 (1991), Rowan et al., Proceedings of SPIE 292 (2003)]

# Bulk Thermal Noise

- Si(111) substrate,  $w = 60$  mm,  $Q = 3 \times 10^8$  (@ 300K),  $Q = 1 \times 10^9$  (@ 18K)



around 18 and 125 K Brownian thermal noise dominates → reduction of thermal noise by use of low loss materials

# Coating Thermal Noise

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- Brownian thermal noise

$$S_x(f, T) \approx \frac{2k_B T}{\pi^2 f} \frac{d}{w^2 Y} \left( \frac{Y'}{Y} \phi_{\parallel} + \frac{Y}{Y'} \phi_{\perp} \right) \quad [\text{Harry et al. 2002}]$$

- thermo-optical noise -> thermoelastic/thermorefractive noise

$$S_{\text{TO}}(\omega, T) \approx \frac{2\sqrt{2}}{\pi} \frac{k_B T^2}{w^2 \sqrt{\kappa C \omega}} \times \left( \alpha_c d - \frac{\partial n}{\partial T} \lambda - \alpha_s d \frac{C_c}{C_s} \right)^2 \quad [\text{Evans et al. 2008}]$$

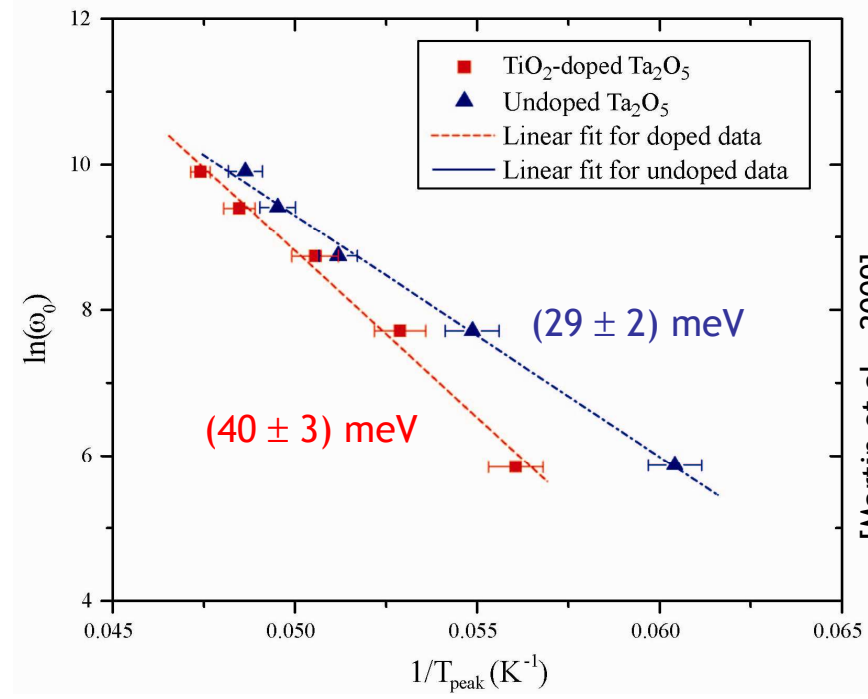
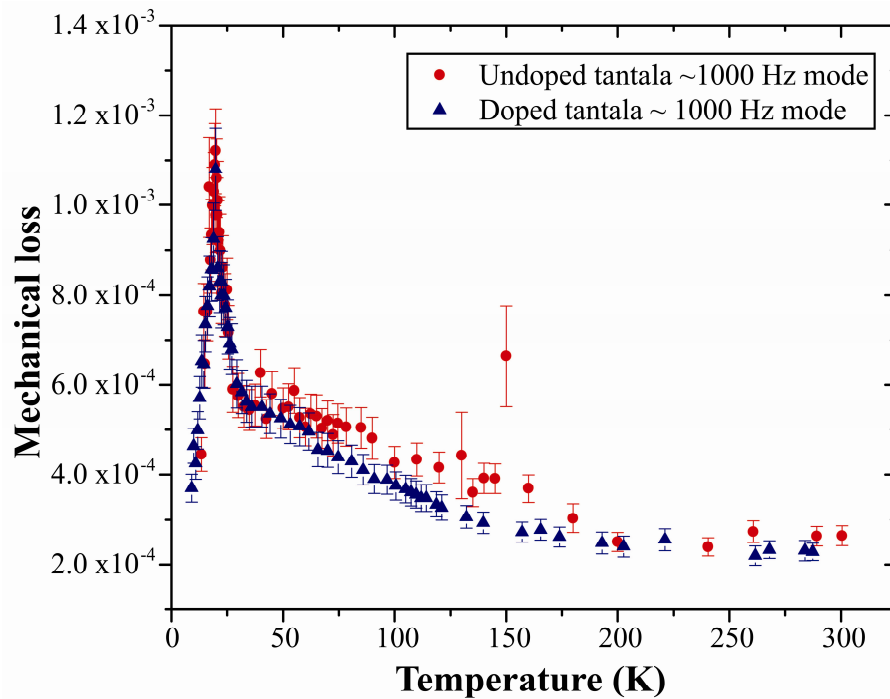
compensation of different contribution is possible

values of the temperature dependence of several properties up to now not available → but: compensation or reduction at cryogenic temperatures expected



# Coating Thermal Noise

- influence of doping on the mechanical losses of coating materials

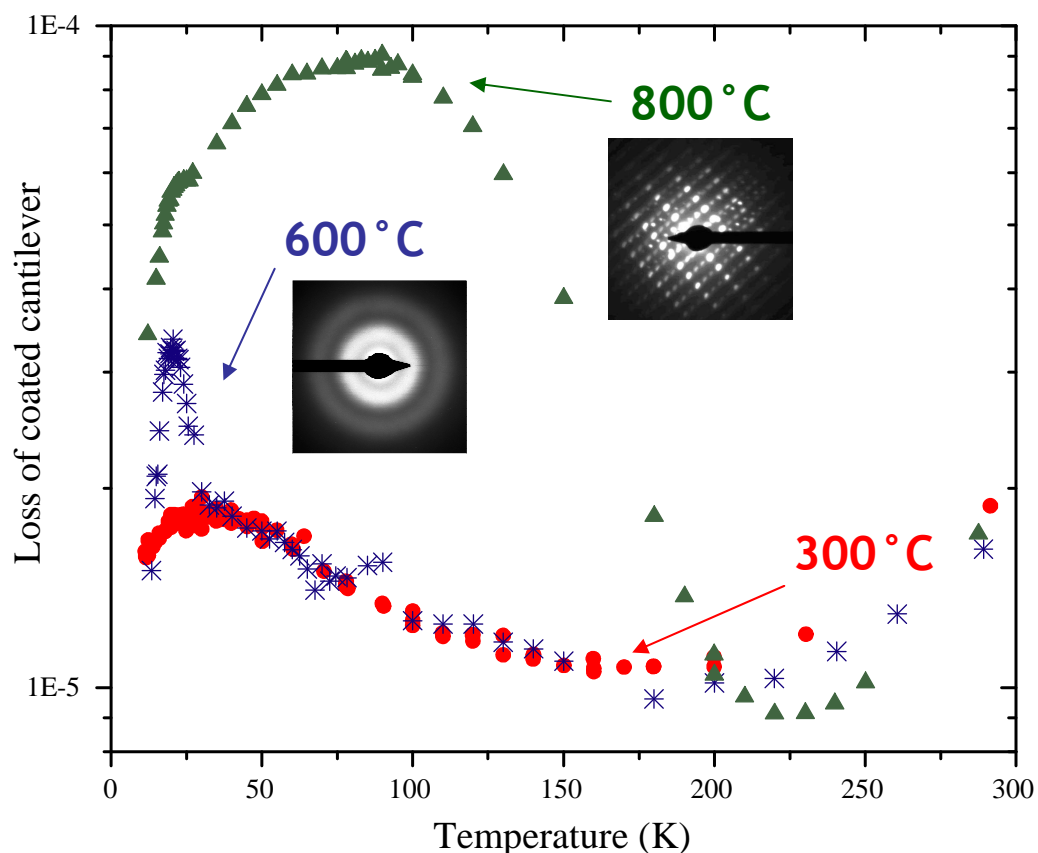


[Martin et al., 2009]

doping changes the microscopic structure  $\rightarrow$  change in activation energy

# Coating Thermal Noise

- influence of heat treatment on the mechanical losses of coating materials



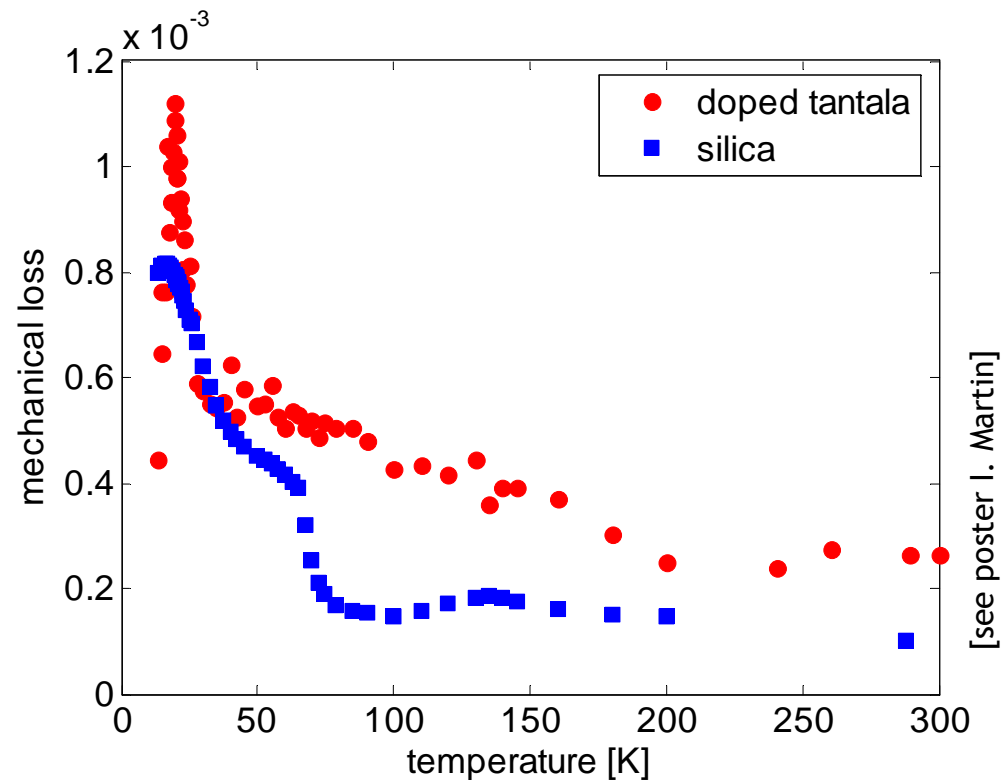
- annealing improves optical properties
- low temperature loss peaks appear during heat treatment ( $T_{\text{peak}} \sim 20 \text{ K}$ )
- electron diffraction reveals crystallisation above  $800^\circ \text{C}$

[see poster R. Bassiri]

[see poster S. Penn]

# Coating Thermal Noise

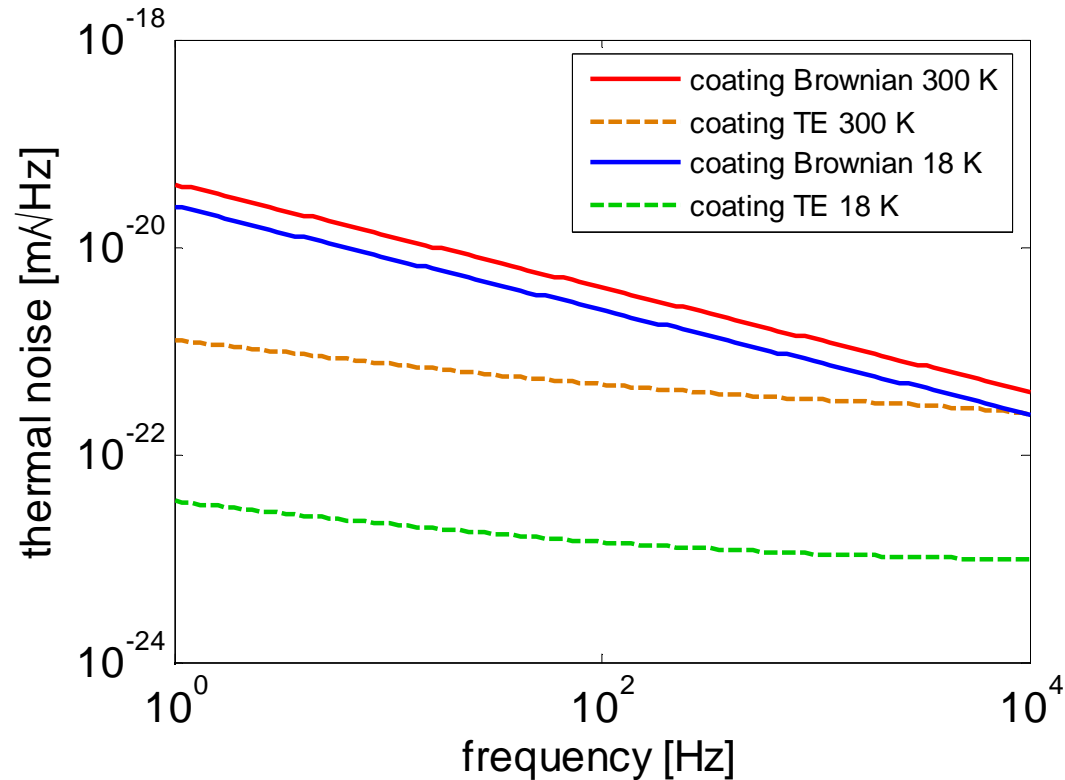
- currently available mechanical loss values



	300 K	18 K
silica	$4 \times 10^{-5}$	$7 \times 10^{-4}$
Ti:Ta <sub>2</sub> O <sub>5</sub>	$2 \times 10^{-4}$	$1 \times 10^{-3}$

increasing loss down to ~ 20 K for both materials

# Coating Thermal Noise

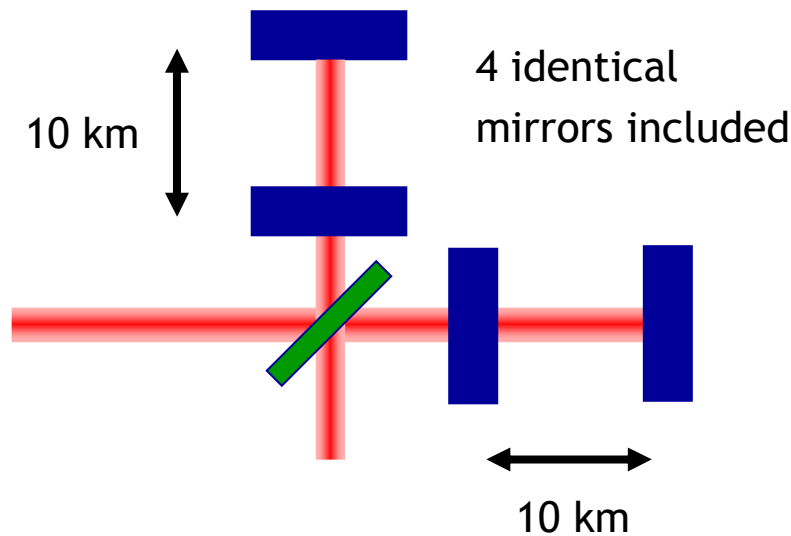


- Brownian thermal noise dominates
- thermoelastic noise is much smaller
- Evans et al. 2008: (partly) cancellation of thermoelastic and thermorefractive noise → Brownian noise remaining relevant noise component

Coating thermal noise is determined by Brownian thermal noise. The loss peaks in the mechanical loss spectrum at around 18 K reduce the expected improvement of the GWD.

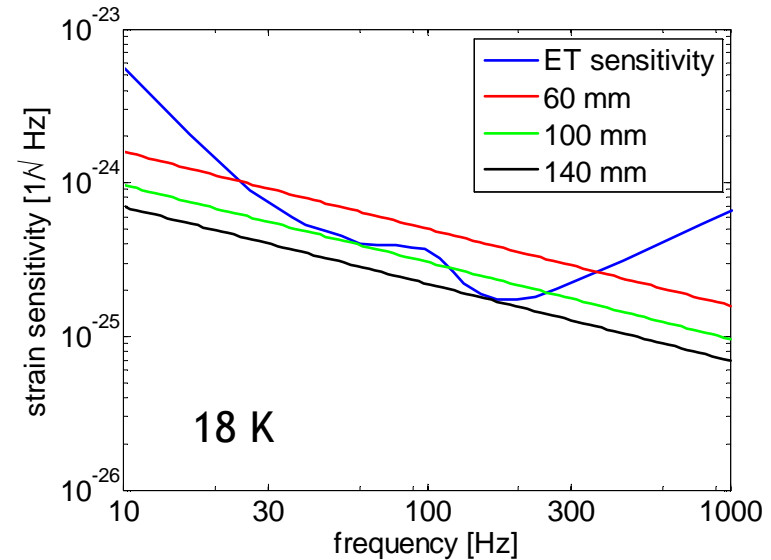
# Design Sensitivity

- in order to achieve the desired sensitivity a larger beam radius is needed



Brownian thermal noise of the coating:

$$S_x(f, T) \approx \frac{2k_B T}{\pi^2 f} \frac{d}{w^2 Y} \left( \frac{Y'}{Y} \phi_{\parallel} + \frac{Y}{Y'} \phi_{\perp} \right)$$

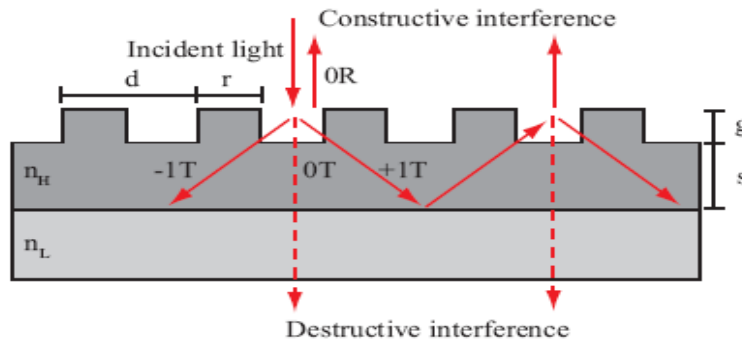


masses up to 500 kg  
needed if an Adv. LIGO  
aspect ratio is assumed

↔ technical limits  
(ROC needed for stable cavity  
not available)

# Novel Approaches

- resonant waveguide

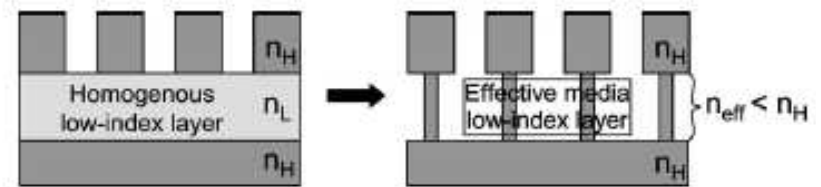


[Brückner et al., Optics Express 17 (2009) 163 - 169]

thickness of tantala by one order of magnitude smaller than in dielectric stacks

reduced thermal noise

- monolithic waveguide



[Brückner et al., Optics Letters 33 (2008) 264 - 266]

no lossy dielectric materials needed, no interfaces, excellent thermal properties

reduced thermal noise

# Resonant Waveguide Concept

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- noise estimation

$$S_x(f, T) \approx \frac{2k_B T}{\pi^2 f} \frac{d}{w^2 Y} \left( \frac{Y'}{Y} \phi_{\parallel} + \frac{Y}{Y'} \phi_{\perp} \right)$$

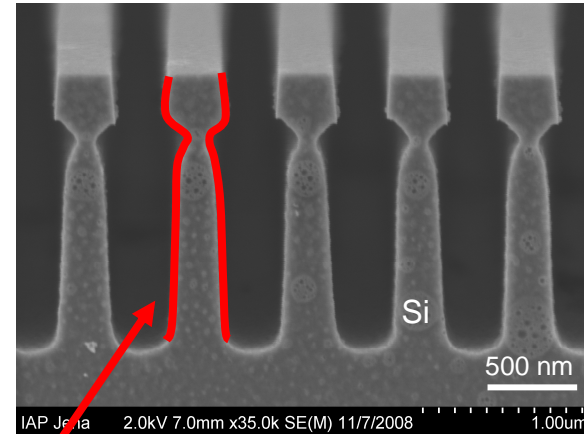
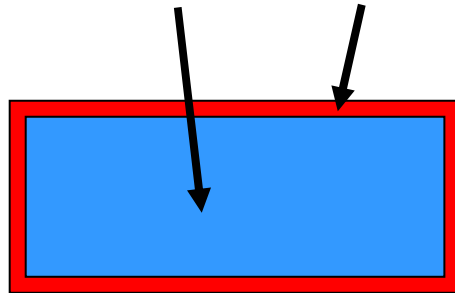
thickness of tantala smaller by one order of magnitude  $\rightarrow$  thermal noise is reduced by  $\sqrt{10}$  (other types of noise much smaller)

- still: optical absorption  $\rightarrow$  heating in the waveguide

# Monolithic Waveguide Concept

- mechanical loss will be influenced by the surface layer

$$\varphi = \varphi_{\text{bulk}} + \varphi_{\text{surface}}$$



- surface is increased compared to bulk samples
- modelling of surface losses similar to fused silica

$$\varphi_{\text{surface}} \sim \frac{S}{V}$$

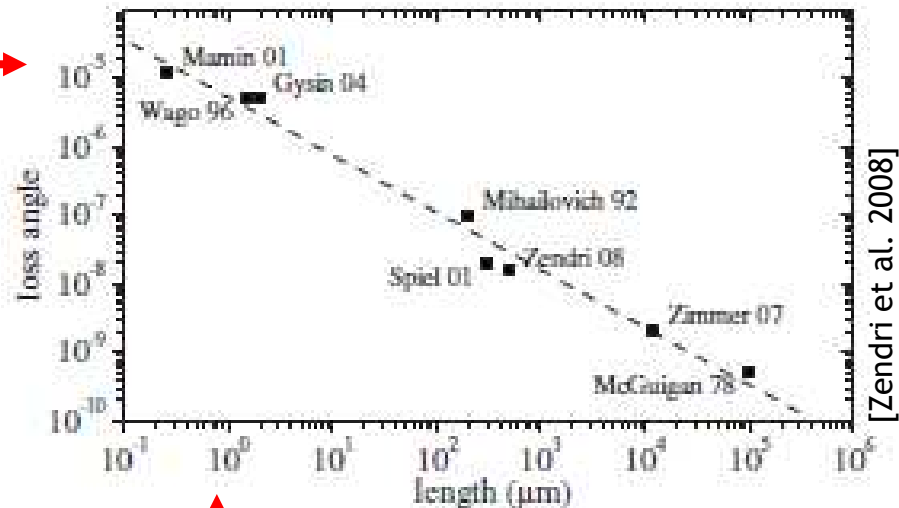
S ... surface area  
V ... volume



# Monolithic Waveguide Concept

- until now no systematic investigation of silicon surface loss (reason: temperature as an additional parameter)
- compilation of several loss measurements vs. smallest dimension of the sample ( $\sim V/S$ )
- temperature  $\sim 1-15$  K

$$\varphi \sim 10^{-5}$$

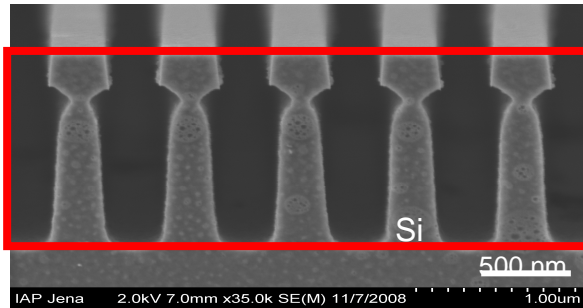


[Zendri et al. 2008]

structure size of the T-structure

# Monolithic Waveguide Concept

- estimation of the Brownian thermal noise at 18 K

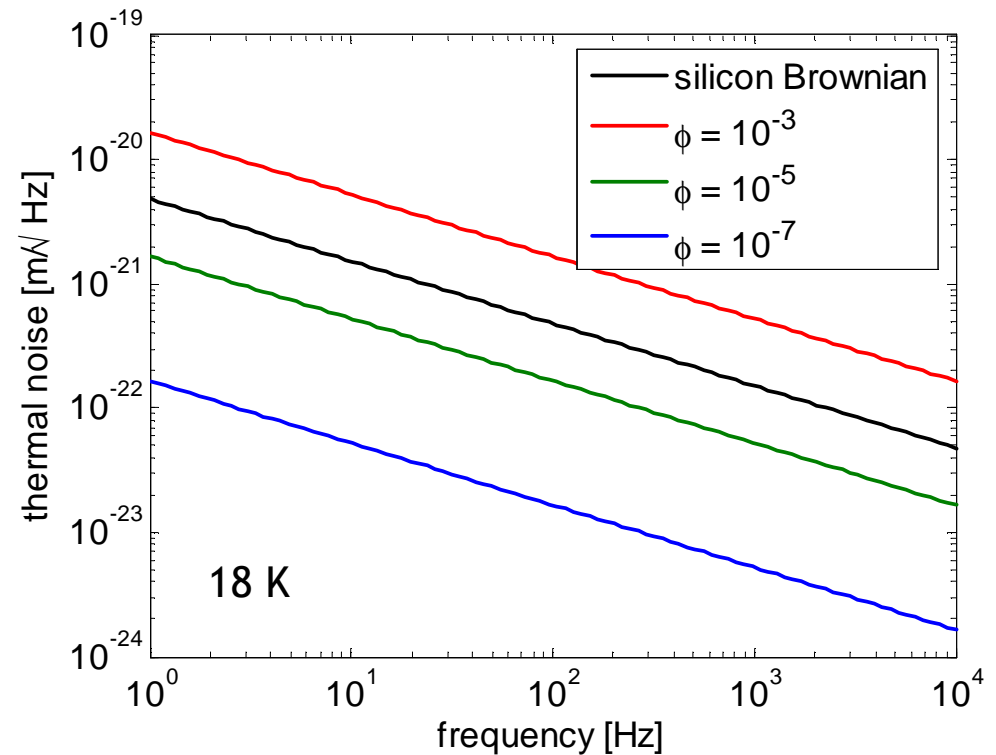


all structures are smaller than the wavelength of the laser light → structure is not resolved by laser → treatment as “effective media”

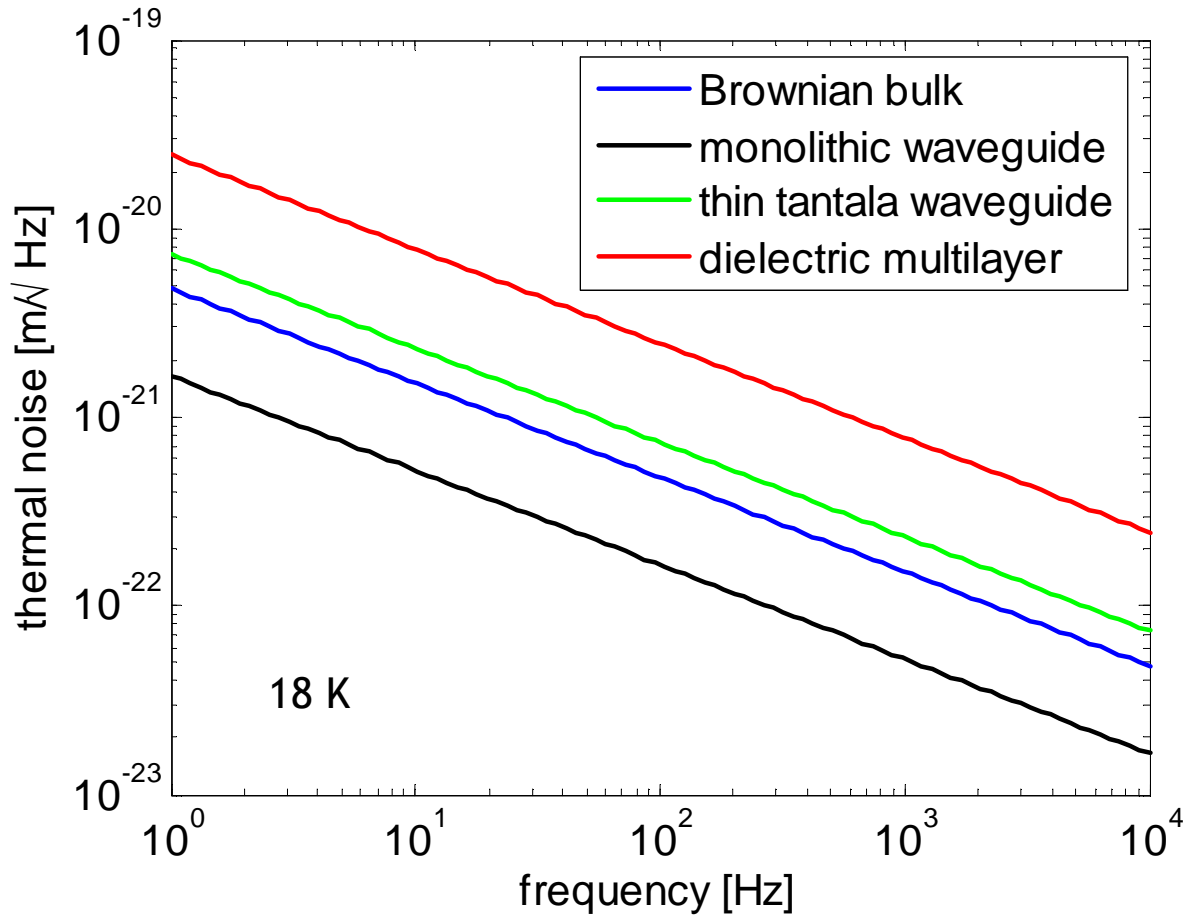
$Y = 100 \text{ GPa}$  (Si: 130 - 188 GPa)

$t = 1.5 \text{ }\mu\text{m}$

volume averaged thermal properties



# Comparison of the different concepts



T-structure adds no significant noise to the bulk Brownian noise

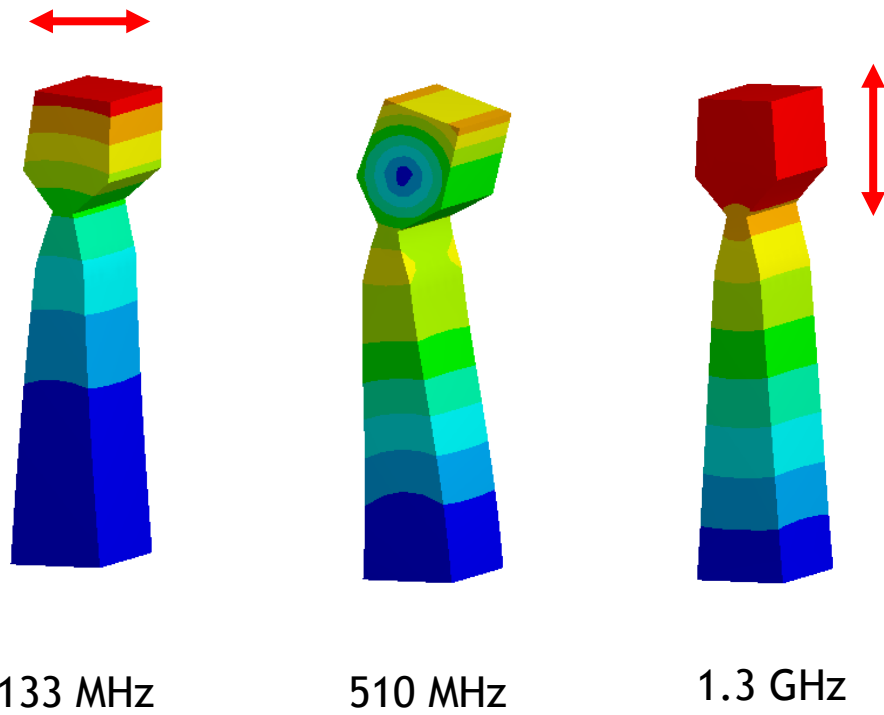


total noise is governed by bulk Brownian noise

# Summary

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- silicon remains an attractive option for a 3rd generation detector substrate material
- dielectric multilayer stacks provide significant Brownian thermal noise of mirrors → large beam diameters needed
- investigation on reducing the mechanical loss by heat treatment is ongoing
- monolithic resonant waveguides provide a low thermal noise concept for mirrors and cavity couplers
- experimental verification of surface loss predictions currently underway
- novel low noise concept for a beamsplitter still needed



# References

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